

10/672,298.

CofC



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Hwang et al.

Attorney Docket No.: KLA1P067/P995

Patent: 7,061,625 B1

Issued: June 13, 2006

Title: METHOD AND APPARATUS USING  
INTERFEROMETRIC METROLOGY FOR HIGH  
ASPECT RATIO INSPECTION

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as first class mail on December 1, 2006 in an envelope addressed to the Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450.

Signed: \_\_\_\_\_

Aurelia M. Sanchez

**REQUEST FOR CERTIFICATE OF CORRECTION  
OF OFFICE MISTAKE  
(35 U.S.C. §254, 37 CFR §1.322)**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450  
Attn: Certificate of Correction

**Certificate  
DEC 07 2006  
of Correction**

Dear Sir:

Attached is Form PTO-1050 (Certificate of Correction) at least one copy of which is suitable for printing. The errors together with the exact page and line number where the errors are shown correctly in the application file are as follows:

**SPECIFICATION:**

1. Column 17, line 52, insert --In an alternative embodiment, two or more image acquisitions may be used to assist in defect detection for different applications and to minimize process noise. That is, by acquiring and storing two different images of the same portion of the wafer sample, for example at two different planes, post processing analysis, such as performed in block 340, may better discriminate between defects and pattern noise. Alternatively, two or more image sensors may be used to inspect the complex field at two different planes, for example by incorporating two sets of optics. Thus, the scope of the invention is not to be limited to a single interferometric microscope module.

DEC - 8 2006

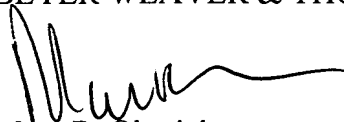
DEC - 8 2006

Although the foregoing invention has been described in some detail for purposes of clarity of understanding, it will be apparent that certain changes and modifications may be practiced within the scope of the appended claims. It should be noted that there are many alternative ways of implementing both the process and apparatus of the present invention. Accordingly, the present embodiments are to be considered as illustrative and not restrictive, and the invention is not to be limited to the details given herein, but may be modified within the scope and equivalents of the appended claims.-- This appears correctly in the patent application as filed on September 26, 2003, on page 38.

Patentee hereby requests expedited issuance of the Certificate of Correction because the error lies with the Office and because the error is clearly disclosed in the records of the Office. As required for expedited issuance, enclosed is documentation that unequivocally supports the patentee's assertion without needing reference to the patent file wrapper.

It is noted that the above-identified errors were printing errors that apparently occurred during the printing process. Accordingly, it is believed that no fees are due in connection with the filing of this Request for Certificate of Correction. However, if it is determined that any fees are due, the Commissioner is hereby authorized to charge such fees to Deposit Account 500388 (Order No. KLA1P067).

Respectfully submitted,  
BEYER WEAVER & THOMAS, LLP



Mary R. Olynick  
Registration No. 42,963

P.O. Box 70250  
Oakland, CA 94612-0250  
650-961-8300

DEC 1 - 8 2006

DEC 1 - 8 2006

In an alternative embodiment, two or more image acquisitions may be used to assist in defect detection for different applications and to minimize process noise.

That is, by acquiring and storing two different images of the same portion of the wafer sample, for example at two different planes, post processing analysis, such as performed in block 340, may better discriminate between defects and pattern noise.

Alternatively, two or more image sensors may be used to inspect the complex field at two different planes, for example by incorporating two sets of optics. Thus, the scope of the invention is not to be limited to a single interferometric microscope module.

Although the foregoing invention has been described in some detail for purposes of clarity of understanding, it will be apparent that certain changes and modifications may be practiced within the scope of the appended claims. It should be noted that there are many alternative ways of implementing both the process and apparatus of the present invention. Accordingly, the present embodiments are to be considered as illustrative and not restrictive, and the invention is not to be limited to the details given herein, but may be modified within the scope and equivalents of the appended claims.

FILED 2006

(Also Form PT-1050)

## UNITED STATES PATENT AND TRADEMARK OFFICE CERTIFICATE OF CORRECTION

PATENT NO. : 7,061,625 B1

Page 1 of 1

DATED : June 13, 2006

INVENTOR(S) : Hwang et al.

It is certified that error appears in the above-identified patent and that said Letters Patent are hereby corrected as shown below:

### In the Specification:

Column 17, line 52, insert --In an alternative embodiment, two or more image acquisitions may be used to assist in defect detection for different applications and to minimize process noise. That is, by acquiring and storing two different images of the same portion of the wafer sample, for example at two different planes, post processing analysis, such as performed in block 340, may better discriminate between defects and pattern noise. Alternatively, two or more image sensors may be used to inspect the complex field at two different planes, for example by incorporating two sets of optics. Thus, the scope of the invention is not to be limited to a single interferometric microscope module.

Although the foregoing invention has been described in some detail for purposes of clarity of understanding, it will be apparent that certain changes and modifications may be practiced within the scope of the appended claims. It should be noted that there are many alternative ways of implementing both the process and apparatus of the present invention. Accordingly, the present embodiments are to be considered as illustrative and not restrictive, and the invention is not to be limited to the details given herein, but may be modified within the scope and equivalents of the appended claims.--

MAILING ADDRESS OF SENDER:

PATENT NO. 7,061,625 B1

Mary R. Olynick  
BEYER WEAVER & THOMAS, LLP  
P.O. Box 70250  
Oakland, CA 94612-0250

No. of Additional Copies

DEC - 8 2006

1

Burden Hour Statement: This form is estimated to take 1.0 hour to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231.